



## Process for the stripper :

### 1. How to Process

- 1) Work in a ventilated area
- 2) Keep room temperature. Do not heat. Do not inhale the gas.
- 3) Strip
  - a) Spreading: Spread the stripper on the SU-8 structures (50~60ml per 4" wafer)  
Let the product react a few minutes to a few hours depending on the structure thickness
  - b) Dipping: better (much better with sonication) Dichloromethane has to be added when the SRGM bath becomes too viscous.
- 4) Rinse with methylene dichloride
- 5) Rinse with acetone if necessary
- 6) Rinse with plenty of water. Rinse with IPA before wafer if necessary.

### 2. Other information for stripper SRGM and methylene chloride (CH<sub>2</sub>Cl<sub>2</sub>)

- 1) Material for stripper vessel
  - Best with glass
  - Plastic is possible if it resists MC. for example HDPE
- 2) Material for waste bottle
  - Best with glass
  - Plastic is possible if it resists MC. for example HDPE
- 3) Cap for SRGM and waste bottle
  - Always closed when not used.
- 4) Storage
  - 4°C to room temperature
  - 30°C max to prevent intense evaporation
  - ventilated place
- 5) How to rinse beakers
  - use hot DIW. Use acetone if necessary.
- 6) Agitation increases the strip rate.
- 7) When there is unstrip, especially in small apertures.
  - To make SRGM less viscous  
=> Add diluted strip  
strip with the original SRGM -> rinse -> dilute strip (SRGM+CH<sub>2</sub>Cl<sub>2</sub>)
  - To remove residue  
=> Heated MC rinse: below 40°C. Be careful not to inhale the gas.  
=> Plasma: a few minutes at 500W. O<sub>2</sub> or CF<sub>4</sub>/O<sub>2</sub> (high etch rate)